



~~THE~~ UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

SHIMIZU et al Atty. Ref.: 829-619; Confirmation No. 2644

Appl. No. 10/735,621 TC/A.U. 1763

For: PLASMA CVD APPARATUS, AND METHOD FOR FORMING FILM AND METHOD FOR FORMING SEMICONDUCTOR DEVICE USING THE SAME

\* \* \* \* \*

July 20, 2006

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

## **AMENDMENT AFTER FINAL**

Responsive to the Official Action dated March 21, 2006 (for which petition is hereby made for a one month extension of time), please amend the above-identified application as follows. *This application places allowable claims in independent form, so that this amendment should be entered and the application is now in condition for allowance given the Examiner's indication of allowable subject matter.*

07/21/2006 SDENBOB1 00000041 10735621

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